



PATENTS

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

KENNETH E. GONSALVES

Serial No. **09/992,560**

Filed: **November 5, 2001**

For: **HIGH RESOLUTION RESISTS
FOR NEXT GENERATION
LITHOGRAPHIES**

Art Unit: **1752**

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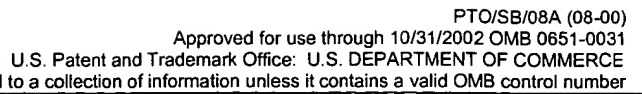
Respectfully submitted,

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Our Docket: 46872-257422

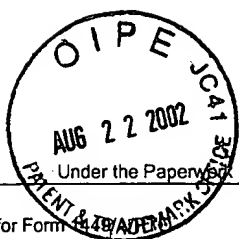
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David E. Wigley, Ph.D. - Reg. No. P52,362



Sheet	1	of	2
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¹Unique citation designation number. ²See attached Kinds of U.S. Patent Documents. ³Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). ⁴For Japanese patent document, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁵Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. ⁶Applicant is to place a check mark here if English language translation is attached.



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**INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**

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Complete if Known

Application Number	09/992,560
Filing Date	November 15, 2001
First Named Inventor	KENNETH E. GONSALVES
Group Art Unit	1752
Examiner Name	
Attorney Docket Number	46872-257422

Sheet 2 of 2

OTHER INFORMATION - NON PATENT LITERATURE DOCUMENTS

Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published

Examiner Initials	Cite No. ¹		T ²
		KENNETH E. GONSALVES, et al., "Combinatorial approach for the synthesis of terpolymers and their novel application as very-high-contrast resists for x-ray nanolithography," J. Vac. Sci. Technol. B 18(1), Jan/Feb 2000, pp. 325-327.	
		YOUNQI HU, et al., "Nanocomposite resists for electron beam nanolithography," Microelectronic Engineering 56 (2001), pp. 289-294.	
		HENPENG WU, et al., "Incorporation of polyhedral oligosilsesquioxane in chemically amplified resists to improve their reactive ion etching resistance," J. Vac. Sci. Technol. B 19(3), May/Jun 2001, pp. 851-855.	
		HENGPENG WU, et al., "Synthesis and Characterization of Radiation-sensitive Polymers and Their Application in Lithography," Ph.D. dissertation, University of Connecticut, April 2001.	
		L. MERHARI, et al., "Nanocomposite resist systems for next generation lithography," Microelectronic Engineering (2002), article in press.	
		JOHN CANNING, "Next generation Lithography: When, why, and at what cost?" Microelectronic Engineering (2002), article in press, abstract only.	
		ROBERT L. BRAINARD, "Resists for next generation lithography," Microelectronic Engineering (2002), article in press.	
		SATOSHI SAITO, "A new positive electron-beam resist material composed of catechol derivatives," Microelectronic Engineering (2002), article in press.	
		HENGPENG WU, et al., "Preparation of a Photoacid Generating Monomer and Its Application in Lithography," Advanced Functional Materials, 11(4), August 2001, pp. 271-276.	
		HENGPENG WU, et al., "A Novel Single-Component Negative Resist for DUV and Electron Beam Lithography," Advanced Functional Materials, 13(3), February 2001, pp. 195-197.	

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